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## **1960's**

### **Clean Bench**

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In 1960, when the manufacture of integrated circuits became full scale, low production yield caused by dust and the like, in particular, in the photolithography process became a big problem, and emphasis was placed on cleaning the manufacturing environment. In around 1960 Fairchild Semiconductor made a device to prevent dust contamination by keeping the interior at positive pressure with a ventilating hood. Eastman Kodak also used this method for photoresist development. It is a prototype of a so-called clean bench. Dust removal is the key to ensuring yield for every work that handles semiconductor wafers, and clean benches became indispensable. After that, the method developed into a clean room system which cleaned the whole room.

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